Cold Start-Up and Operation Procedure for Plasmatherm Shuttlelock SLR-730-PECVD

First-Check before starting a process

- 1) Switch on the main power to tool.
- 2) Check ventilation
- 3) Ensure all water supplies are turned on, water to chiller and the chiller itself.
- 4) Turn on nitrogen and compressed air
- 5) Turn on compressed air *steps (2) (5) explained with more details in the PPT file

Wafer Processing

- 6) Turn on the machine power, mechanical pump power, and lock pump power in PECVD
- 7) Turn on the computer power and launch the program
- 8) Turn on the RF power and Substrate power
- 9) If the chamber is not vented. Go to **Utilities, Vent**. Wait until the chamber is vented and load sample.
- 10) Go to **Utilities-Pump Chamber (Lovac).** Hold chamber lid down and let the vacuum take hold.
- 11) Go to **Process-Load**. Enter desired recipe to run,
- 12) Go to **Ready**
- 13) Go to **Run**. The process will start by running the loaded process.
- 14) Should an alarm be detected, the nature of the alarm will be displayed in the Info' line near the bottom of the monitor screen (Graphic User Interface GUI). This alarm needs to be acknowledged by clicking on the "Alarm" button located at the bottom r/hand corner of the GUI, after clicking on the alarm button the alarms sounder will cease and the "Hold" button will also be highlighted. The alarm will need to be resolved before this procedure can progress. Once the alarm has been resolved, click the "Hold" button and this will clear both the highlighted Alarm and the Hold buttons.
- 15) When finished go to **Pump Chamber (Lovac).**
- 16) When finished with a group of samples, run a chamber clean process,
- 17) Go to **Standby**.
- 18) Shut off Nitrogen Purge.